



Scuola Superiore ISUFI
Nanoscience Grid-Computing Section

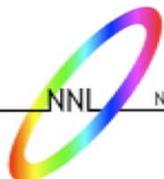


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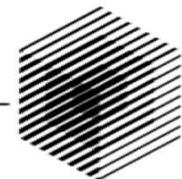
Nanostrutture a confinamento quantistico elettronico: i quantum dot

Massimo De Vittorio

*National Nanotechnology Laboratories of CNR-INFN
ISUFI - Università del Salento
massimo.devittorio@unile.it*

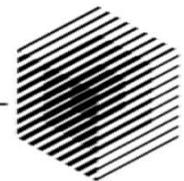
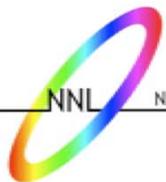


NNL National Nanotechnology Laboratory of I.N.F.M.



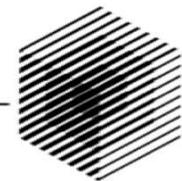
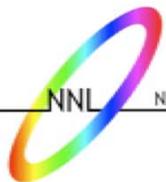
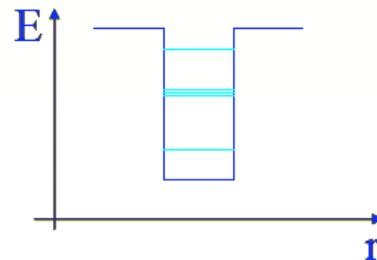
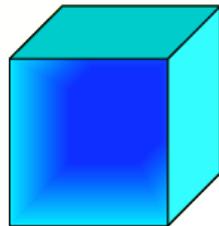
Outline

- Properties of quantum dots (QDs)
- Synthesis of quantum dots
 - *Self organized epitaxial quantum dots*
 - *Colloidal quantum dots*
- Device and applications of different types of quantum dots
- Conclusions



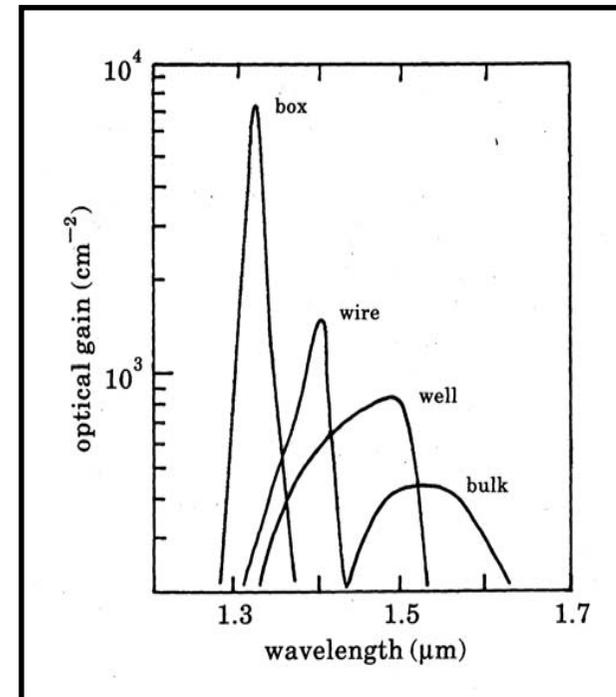
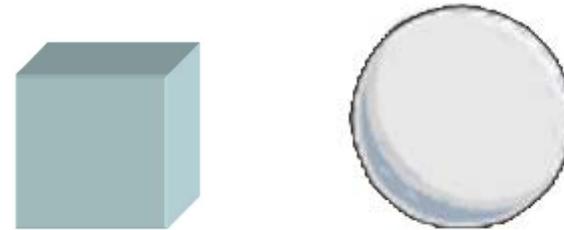
What is a quantum dot

- A confining potential in three dimensions whose size has no sharp definitions
- Wave nature of carriers is important (of the order De Broglie wavelength ~ 10 nm in InAs)
- Discrete states (Artificial atoms)
- Quasi zero-dimensional systems

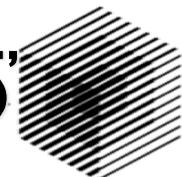
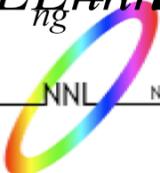


The ideal QDs

- Precise size and shape (box or sphere) with uniform composition
- Infinite quantum confinement
- Array of identical quantum dot
- For a cubic dot (size L):

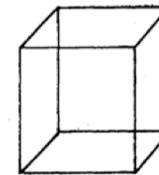


$$E_{ng} = \frac{9 \hbar^2 M}{22 m L^2} \left(\frac{2\pi}{L} \right)^2, 3$$

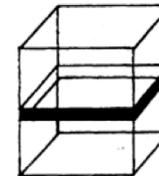
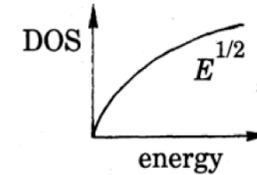


Properties of quantum dots

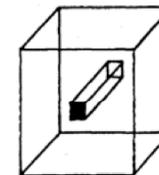
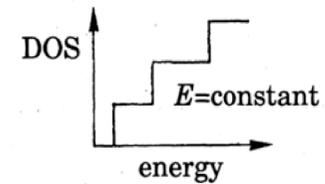
- Delta Function DOS
- Ground state above Bandgap
- Less active states than a bulk device of the same size
- High material gain
- Narrow and symmetrical gain
- Low optical density
- Gain saturation
- Difficult technology



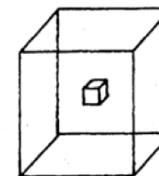
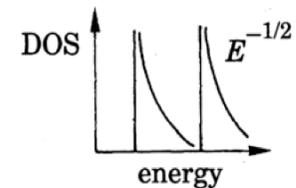
bulk (3D)



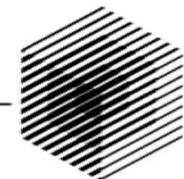
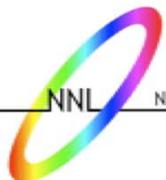
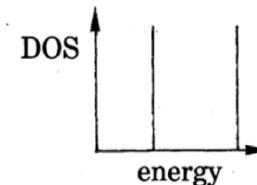
quantum well (2D)



quantum wire (1D)

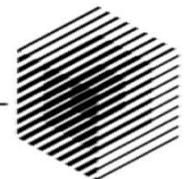
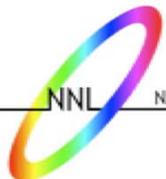


quantum dot (0D)



Applications of epitaxial QDs

- Improve existing devices:
 - Lasers and MCLEDs
 - Optical amplifiers
 - Long Wavelength detectors
- Novel devices and applications
 - Spintronics
 - Quantum computing
 - Quantum cryptography (single photon emitters)
 - Optical memories
- Unique physics compared to bulk semiconductors materials



SEMICONDUCTOR QUANTUM DOTS BASED PHOTONIC DEVICES

Telecommunications and information technology demand fast and reliable data exchange on wide-world area networks

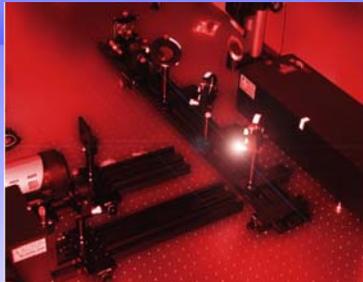
Display and Lightning technology looking for bright, high-resolution, multi-color or white emitting light sources

Pioneering studies on quantum cryptography and non-classical photon sources

Development of optical data transmission systems requiring:

- low-cost
- 1.3 μm emitting
- spectrally pure
- low-power operating
- temperature insensitive
- fast modulating

LASER SOURCES



Development of:

- cheap
- spectrally tunable
- long-lasting
- bright
- controlled at micron-scale

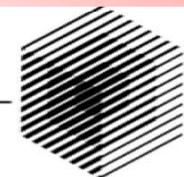
LIGHT SOURCES



Development of:

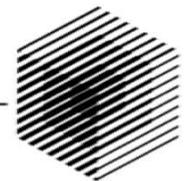
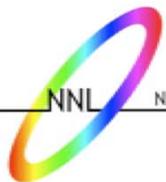
- reliable
- spectrally ultra-pure
- long-lasting
- room-temperature working

PHOTON SOURCES



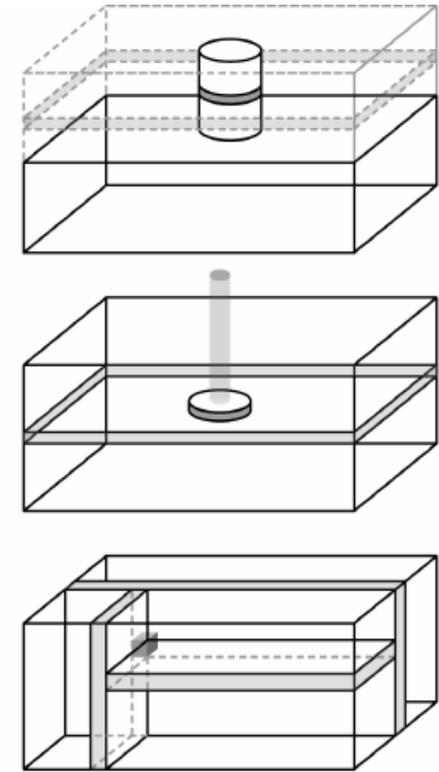
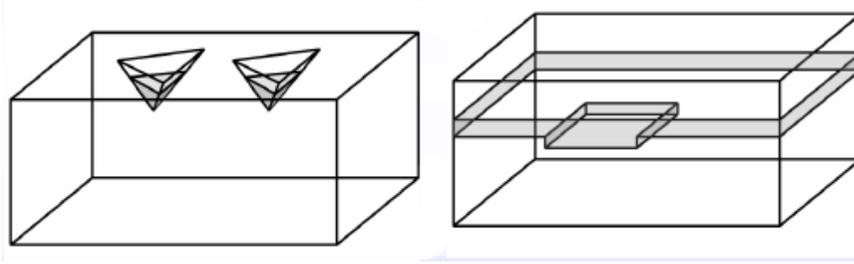
Synthesis of QDs

- Top-down approach
- Self-organization: Stranski Krastanov epitaxial growth
- Colloidal quantum dots



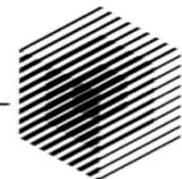
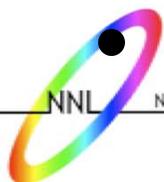
Top-down approach for QDs

- slow process, difficult to have large amount of QDs
- Uniform QDs (limit by lithography)
- Defect states at interfaces due to etching



Bottom-up synthesis of QDs

- Colloidal quantum dots
- Stranski Krastanov epitaxial growth



Bottom-up synthesis of QDs

Epitaxial QDs

✓ Stranski-Krastanow growth

× Growth facilities: Metal-Organic Chemical Vapor Deposition (**MOCVD**) / Molecular Beam Epitaxy (**MBE**)

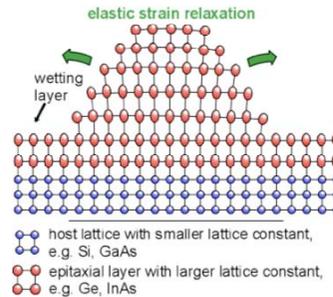
× pyramidal-shaped or lens-shaped islands; **lateral size ~ 10-40 nm** and **heights ~5-8 nm**

× **room-temperature emission** from single QD **difficult** to be achieved due to phonons energy comparable with allowed energy levels distance

✓ **complete burying of QDs into solid crystalline matrix**: low surface defects, high photostability, high radiative recombination rates

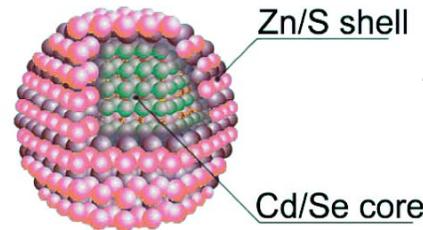
✓ **efficient electrical injection** by p-n doping of the surrounding heterostructure

× **size fluctuation in QD layers**: **inhomogeneous broadening**



Colloidal QDs

✓ Wet-chemical synthesis



✓ Growth facilities: Schlenk line, liquid solution / **Low-cost** and **high throughput** fabrication method

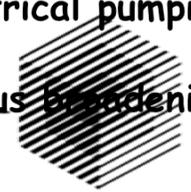
✓ spherical shape with **diameter ~ 2-6 nm**

✓ higher distance among allowed energy states in conduction and valence bands: intense emission also at **room temperature**

× lack of a solid matrix: **spectral shifting** and **blinking** of the single emitter / Need to insert QDs from liquid solution to solid matrices

× easy optical pumping / **not straightforward electrical pumping**

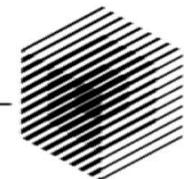
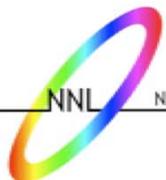
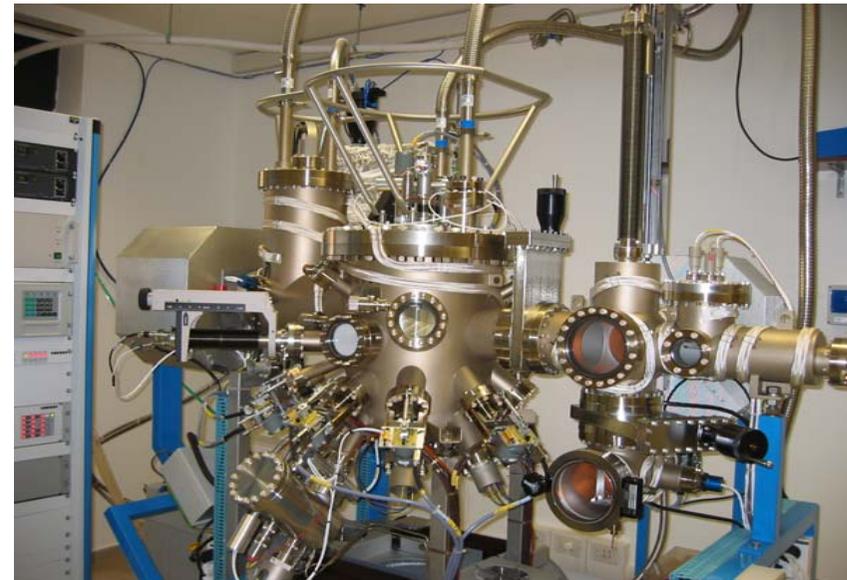
× **inhomogeneous broadening**



Epitaxial growth techniques: MOCVD e MBE

Differences:

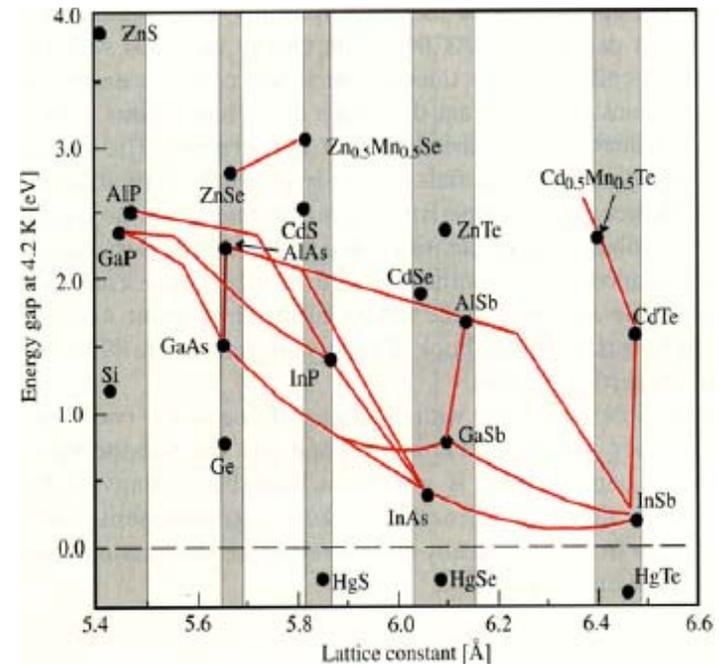
- Growth rate
- UHV and situ monitoring
- safety and materials



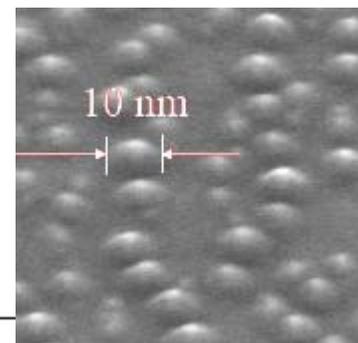
Self assembled QDs

Epitaxial growth: Interplay of surface energy and strain

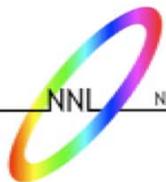
"Standard" (Frank-van der Merwe) 2D epitaxial growth:



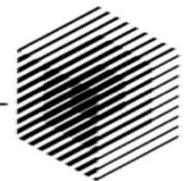
Stranski-Krastanov 3D growth mode (strain-driven):



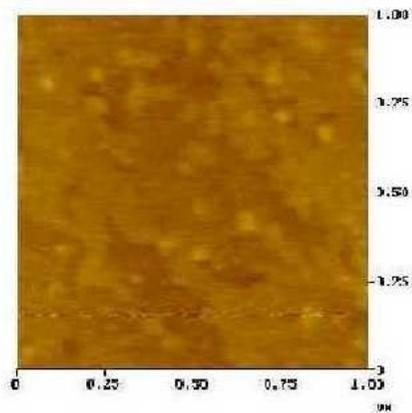
MOCVD QDs



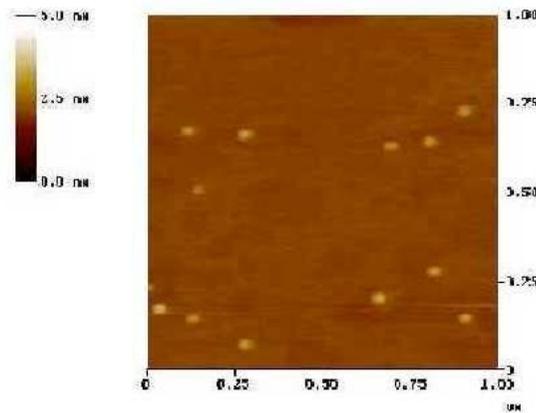
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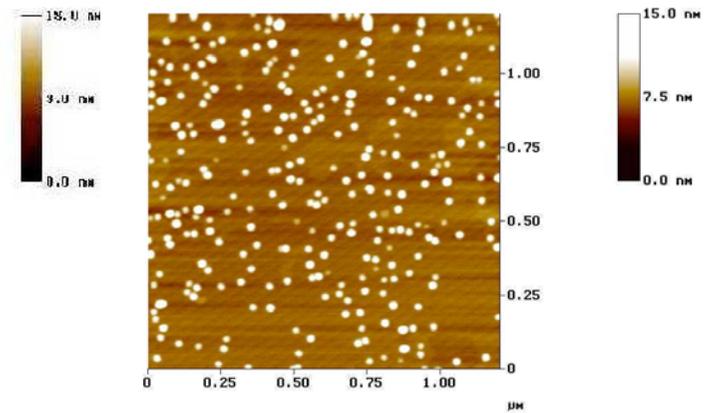
EFFECT OF THE GROWTH RATE



G.R.=0.4 ML/s

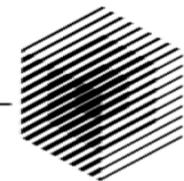
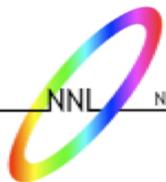


G.R.=1 ML/s
 $r \approx 17 \text{ nm}$

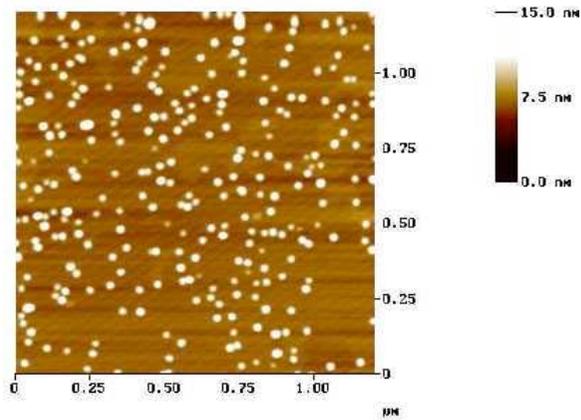


G.R.=2 ML/s
 $r \approx 11 \text{ nm}$

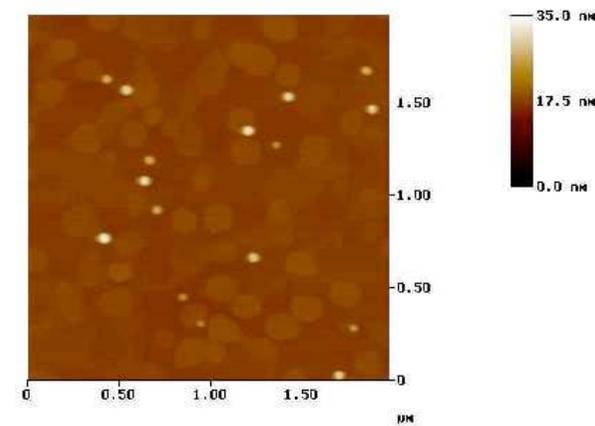
6ML QDs, $T=550 \text{ }^\circ\text{C}$



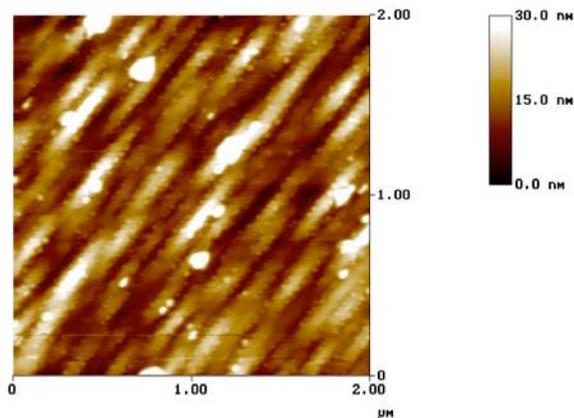
Effect of the Growth Temperature



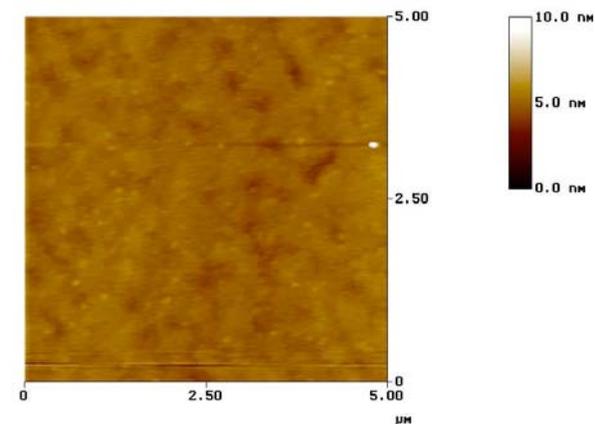
T=550 °C – Gr=2 ML/s



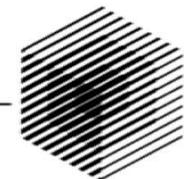
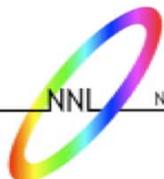
T=600 °C – Gr=2 ML/s



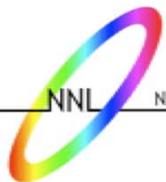
T=530 °C – Gr=0.4 ML/s



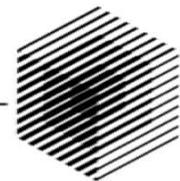
T=580 °C – Gr=0.4 ML/s



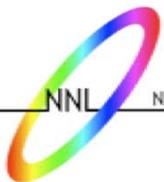
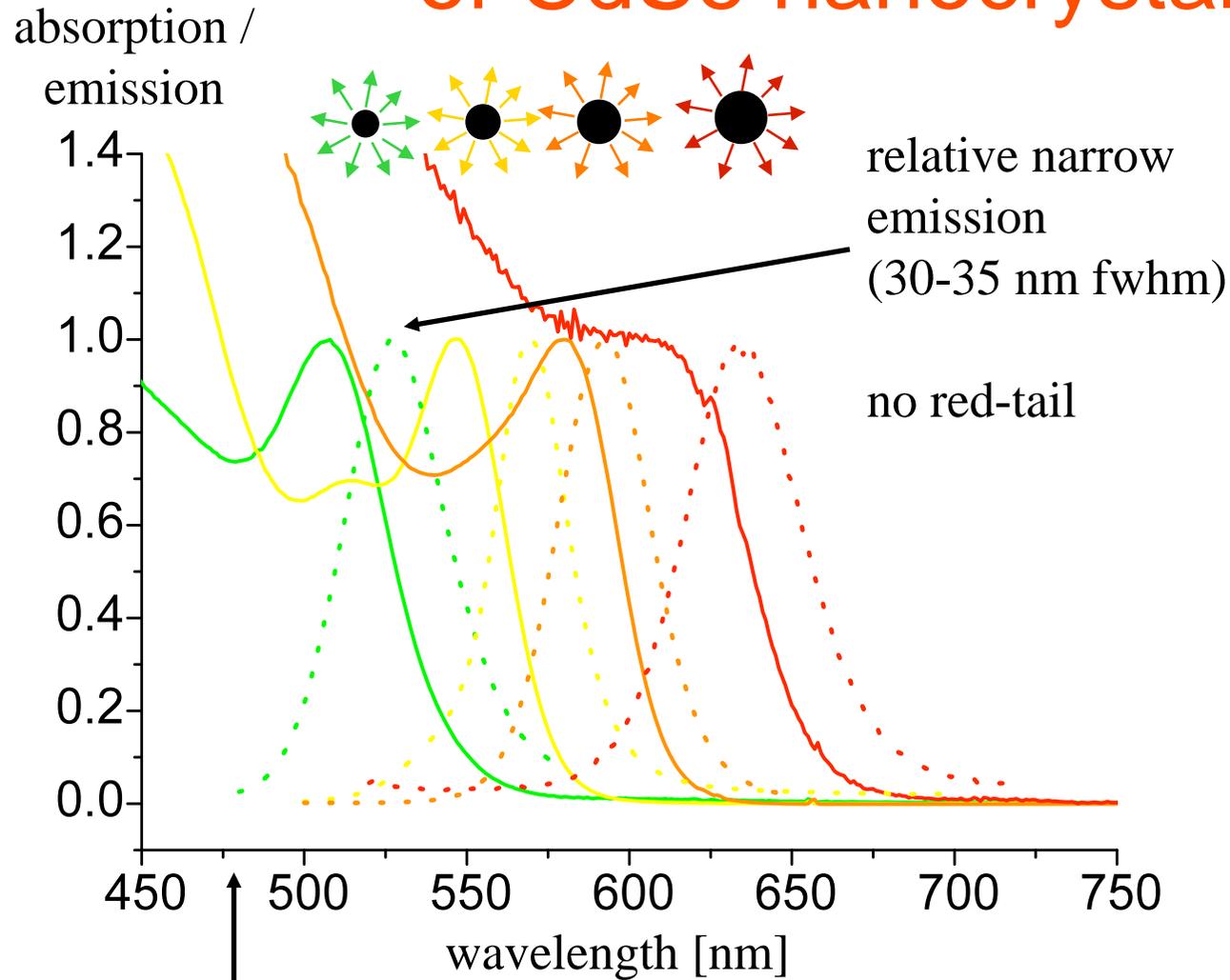
Synthesis of Colloidal Quantum dots



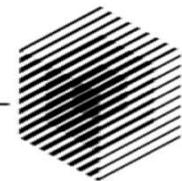
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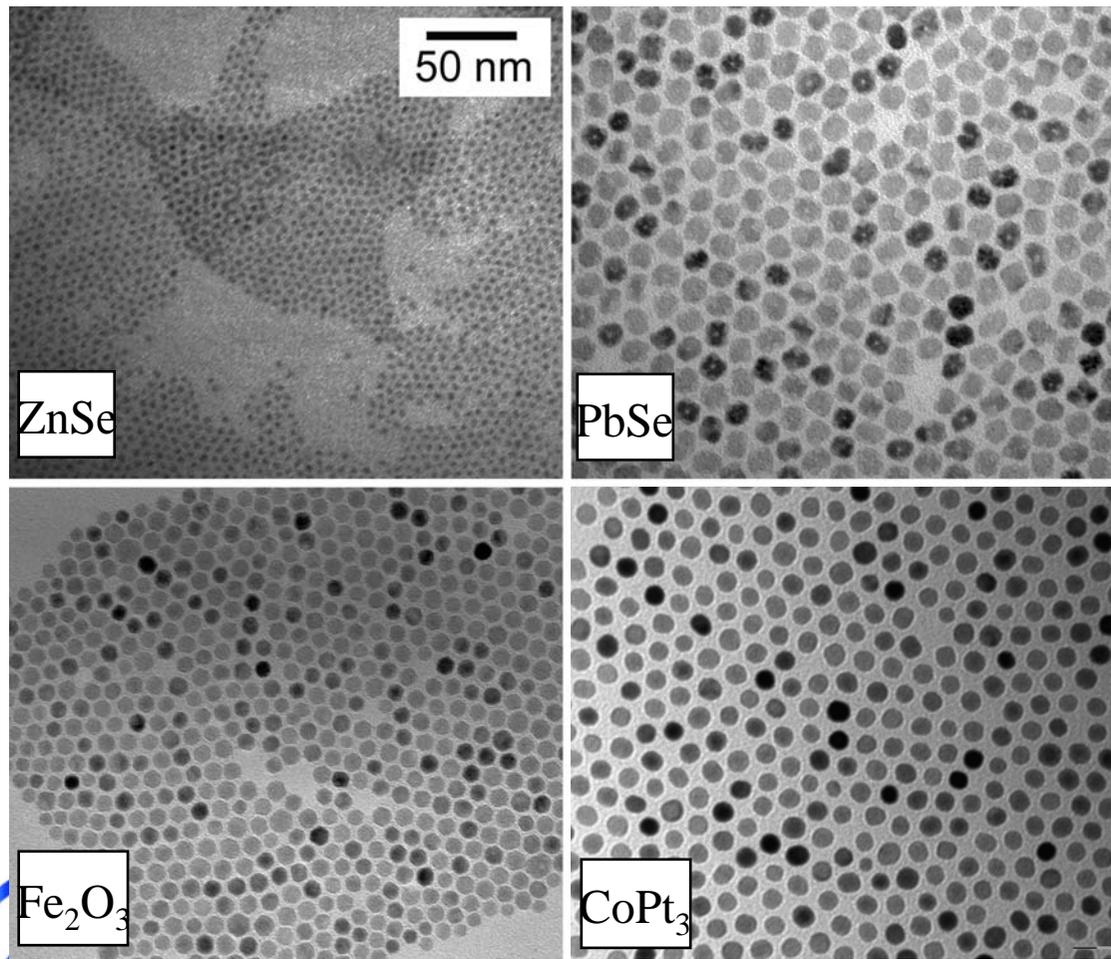
Size dependent photoluminescence of CdSe nanocrystals



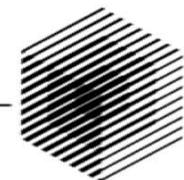
National Laboratory of Nanotechnology (NLT) NNL
all colors can be excited with one single wavelength



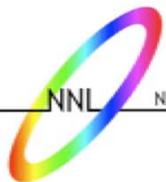
Nanocrystal size control: Colloidal nanocrystals of different materials



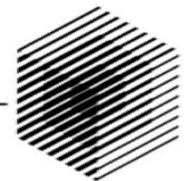
CdSe nanocrystals



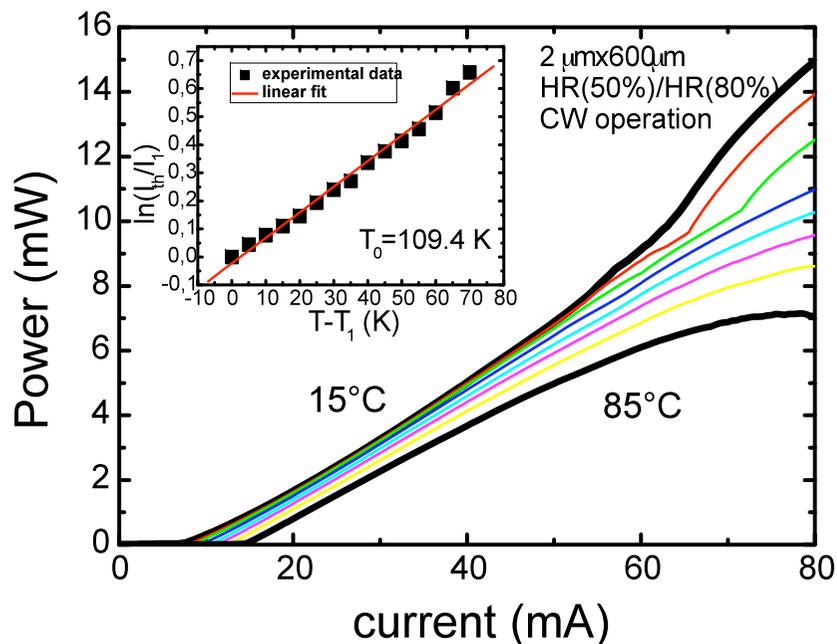
Epitaxial quantum dot devices for telecom applications



National Nanotechnology Laboratory of I.N.F.M.

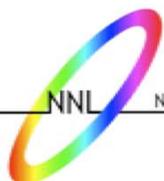
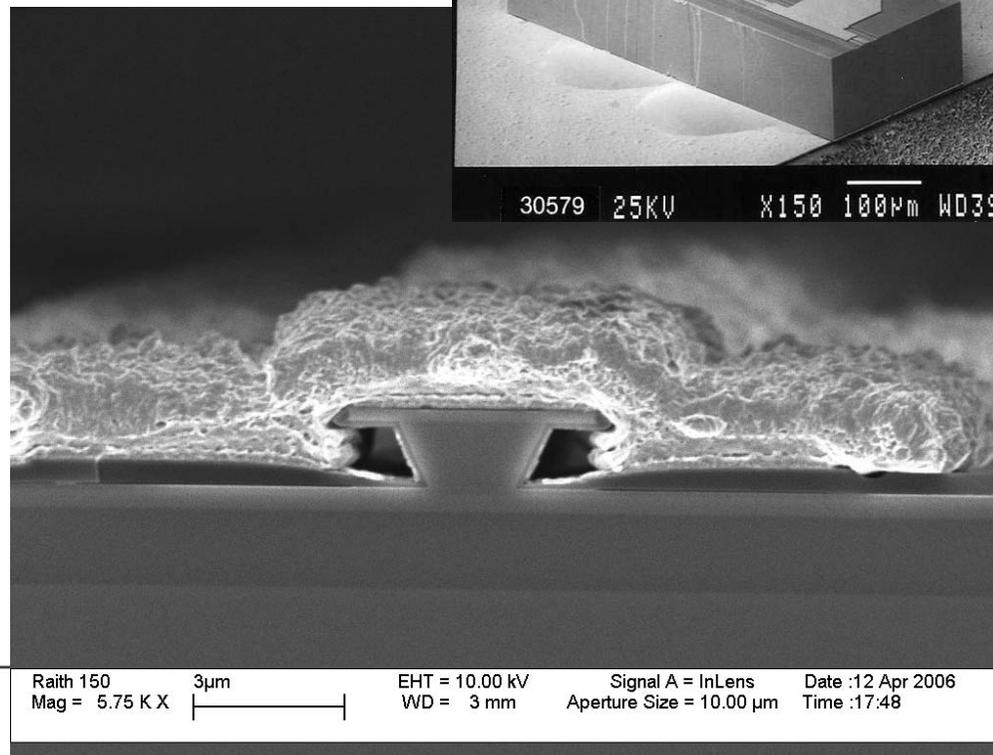
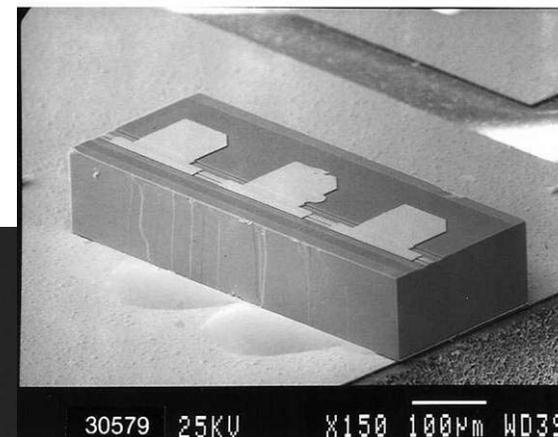


Single-mode QD lasers

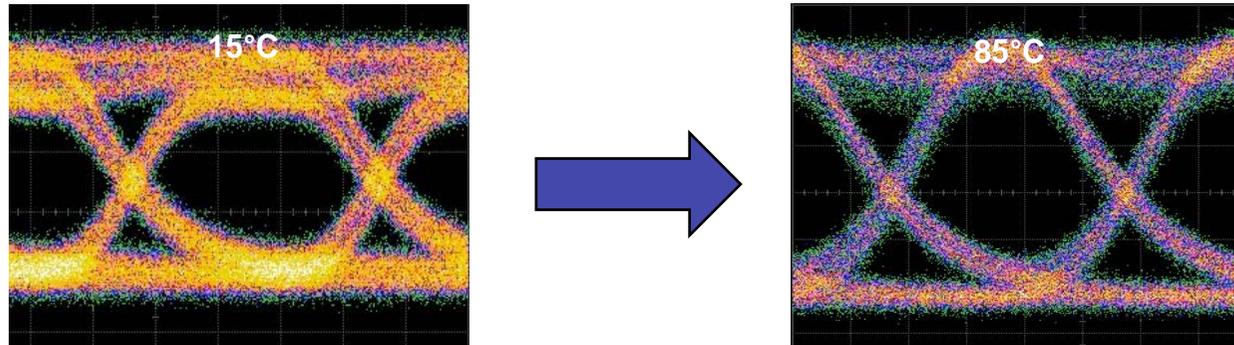


internal losses of 4.8 cm^{-1}
internal quantum efficiency of 23%

The saturation modal gain of the ground state results to be $36.3 \text{ cm}^{-1} \rightarrow 6 \text{ cm}^{-1}$ per QD layer

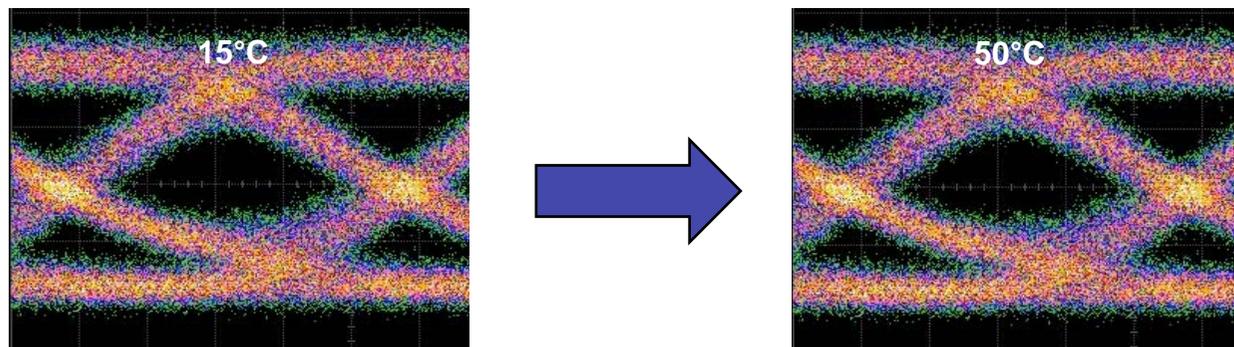


High modulation frequency eye patterns



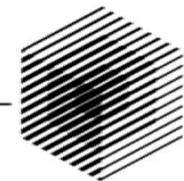
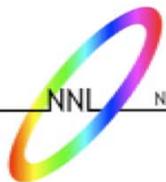
Temperature dependence of eye patterns @ **5 Gb/s**

Extinction ratio of 5 dB @ 15°C and 6 dB @ 85°C

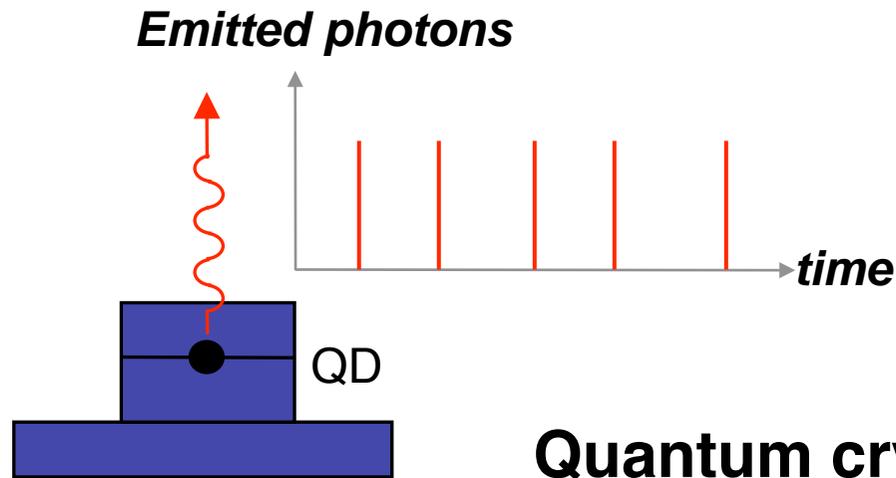


Temperature dependence of eye patterns @ **10 Gb/s**

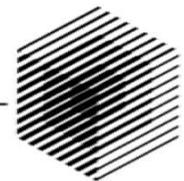
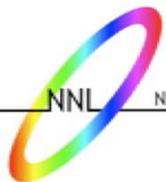
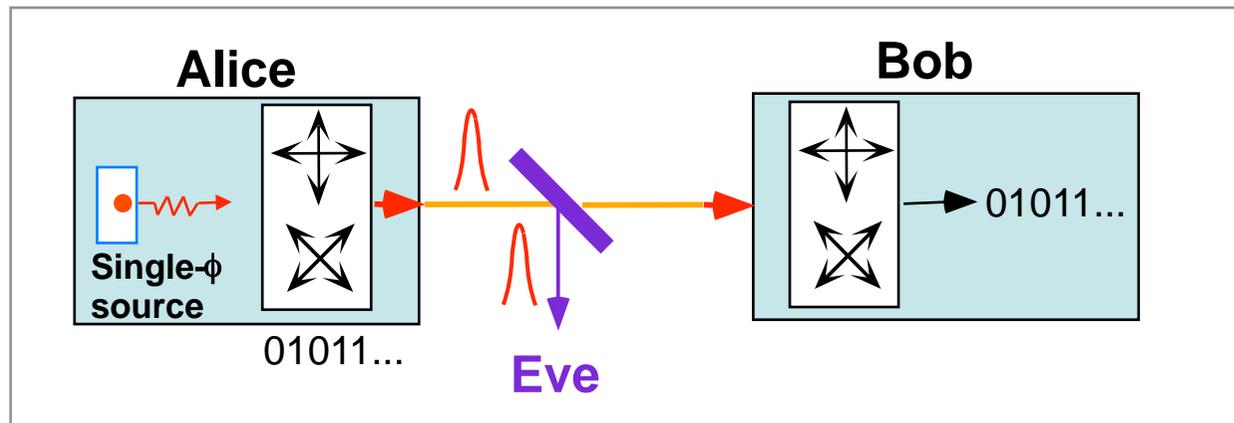
Extinction ratio < 5 dB @ 50°C



Single photons from single QDs

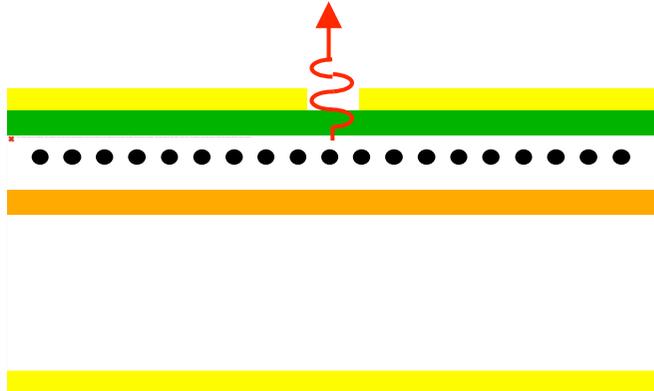


Quantum cryptography:



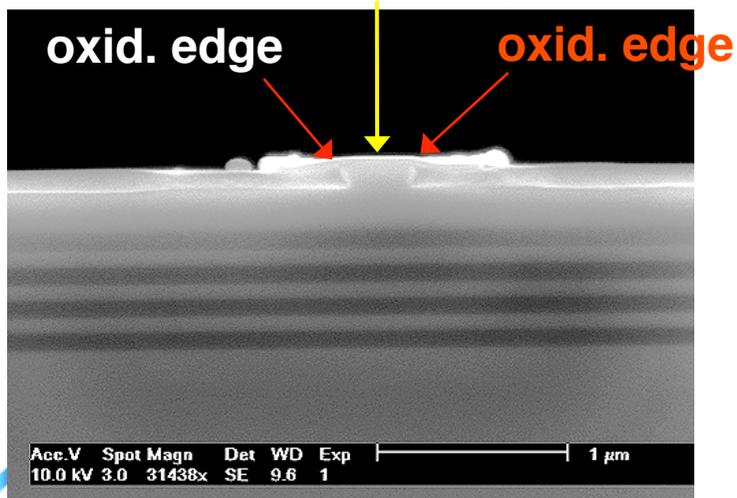
Single QD devices

Shadow-mask LED:

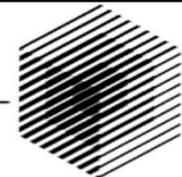


diffusion suppressed (<100 nm) in QDs due to carrier confinement

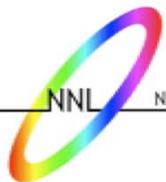
300 nm current aperture



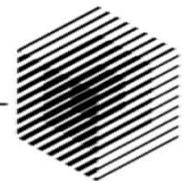
- *Down to 100 nm* current apertures with simple optical lithography
- Can tailor both **current and optical confinement**
- **Bandgap engineering** to reduce current spreading

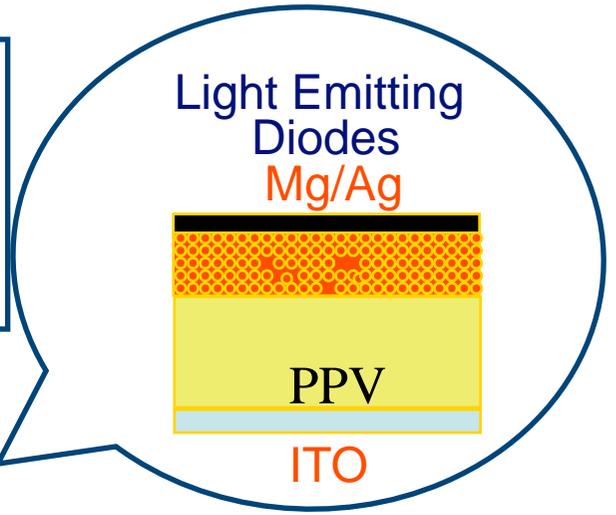
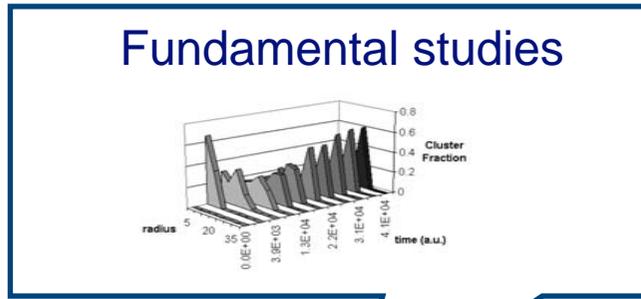
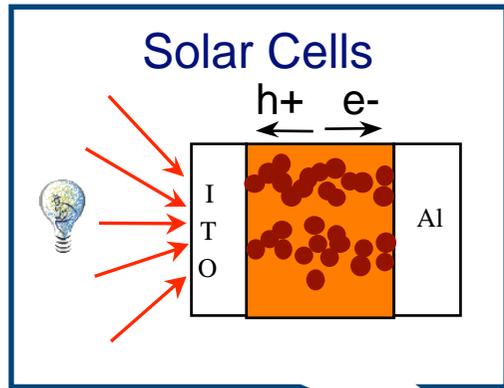


Colloidal NCs devices and applications

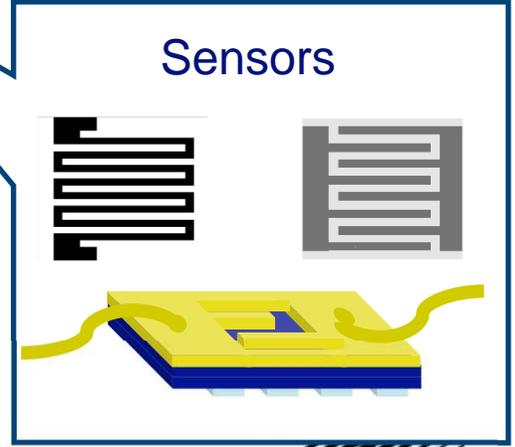
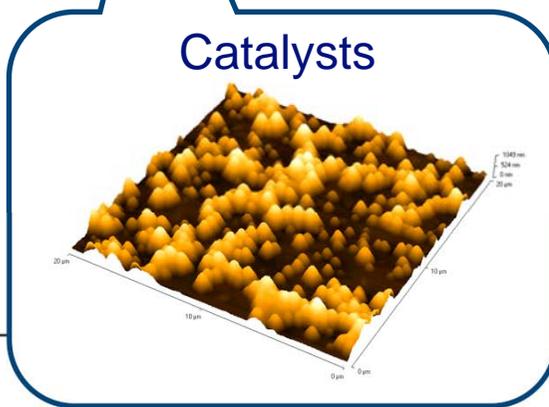
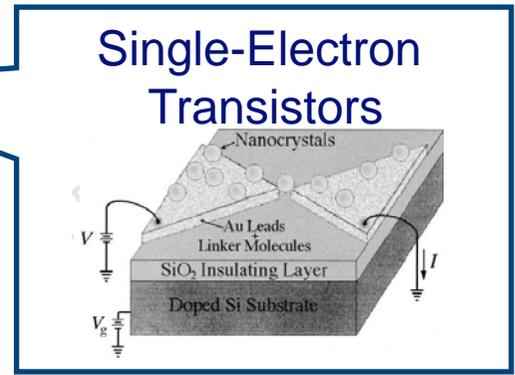
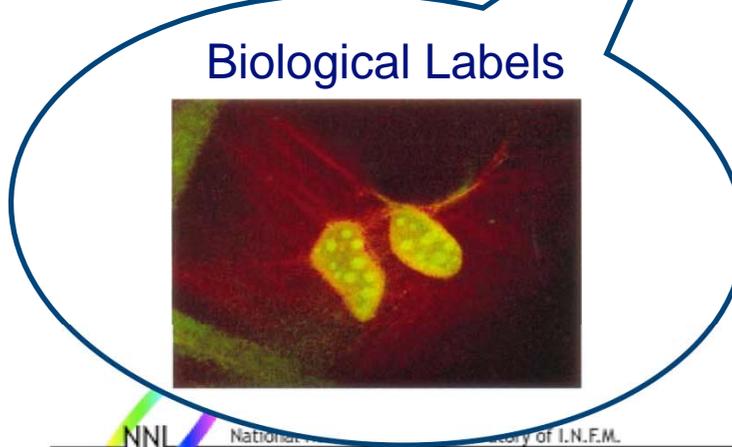
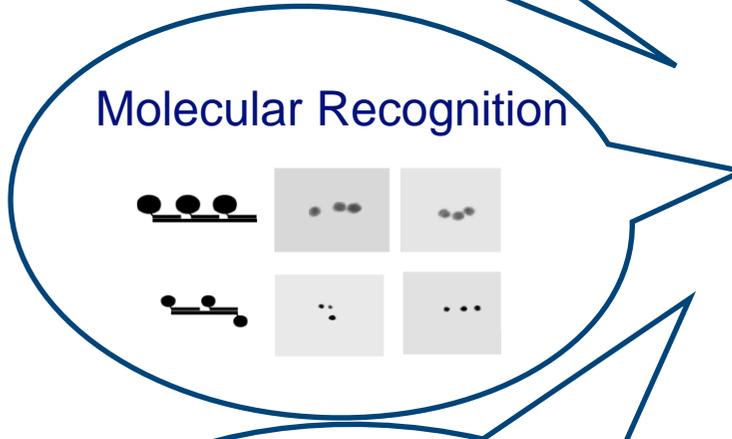
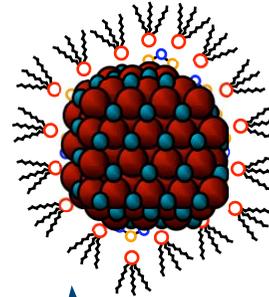


NNL National Nanotechnology Laboratory of I.N.F.M.

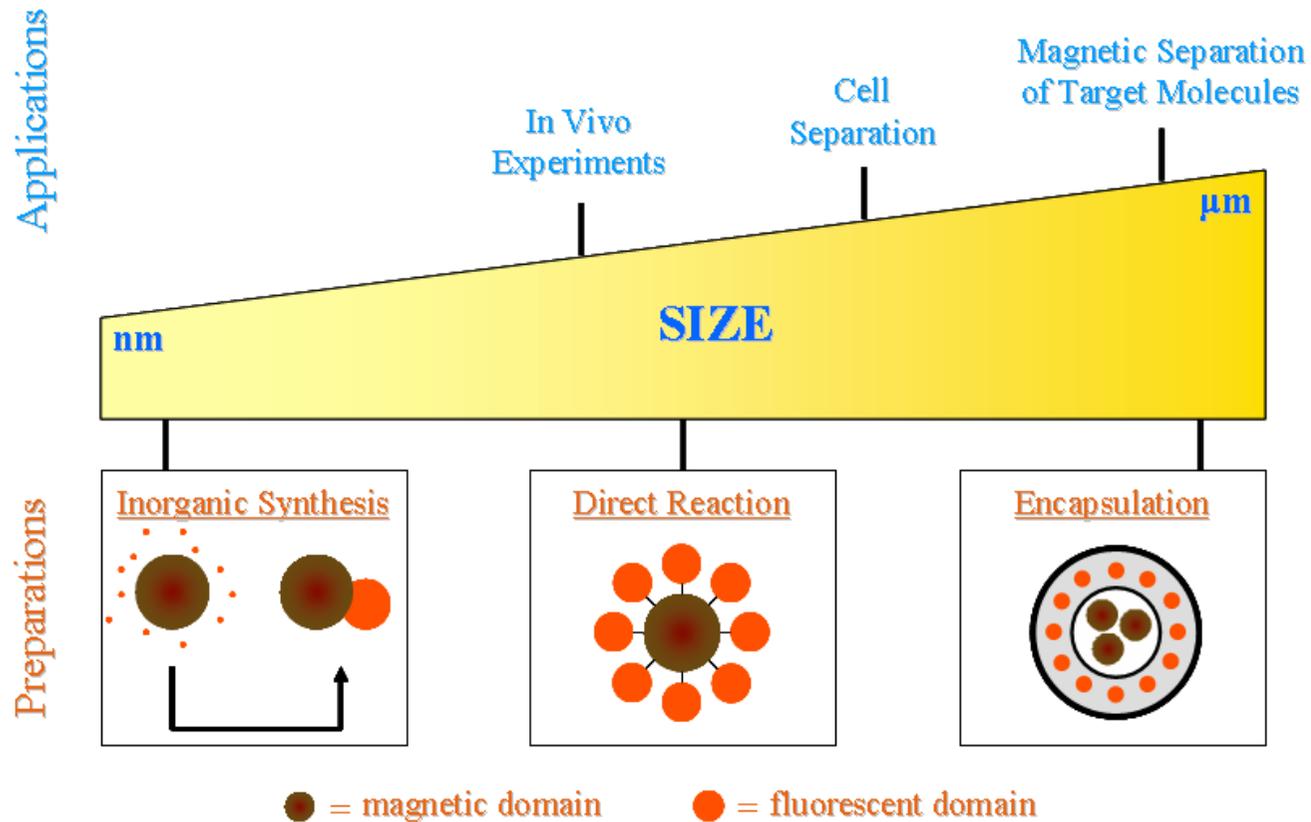




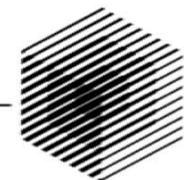
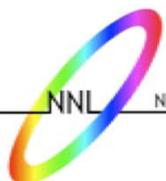
Nanocrystals



Hybrid nanocomposites: magnetic and fluorescent properties combined into one single nano-object



A. Quarta, R. Di Corato, L. Manna and T. Pellegrino, Fluorescent magnetic hybrid nanostructures: preparation, properties and applications in biology, IEEE Transaction in Nanobiotechnology, *in press*

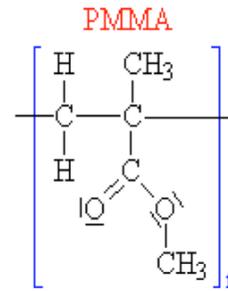
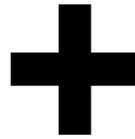


NCs dispersed in resist (ER) matrix

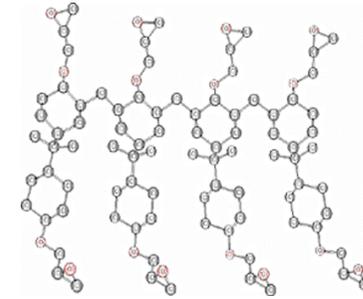


CdSe/ZnS
nanocrystals

Gain material deposited
by
means of low-cost
techniques



poly(methylmethacrylate)



SU-8(epoxy resist)

Sensitive to electron beam or UV
radiation

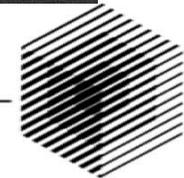
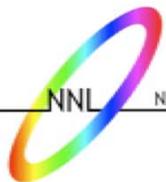
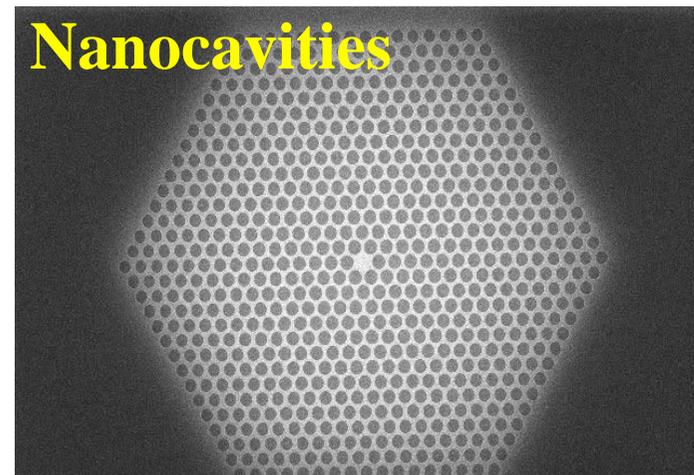
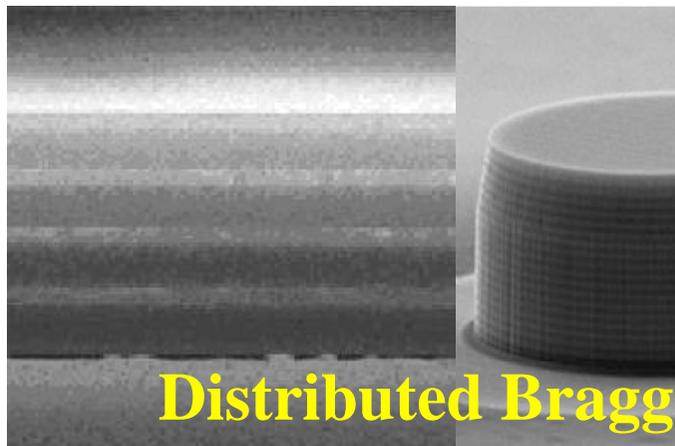
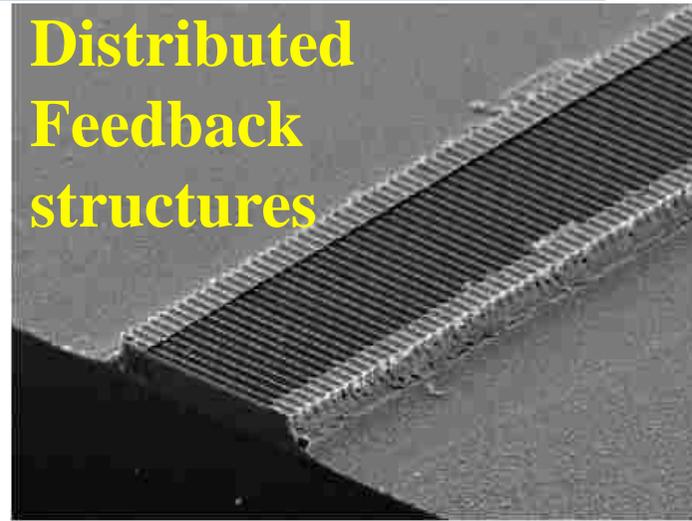
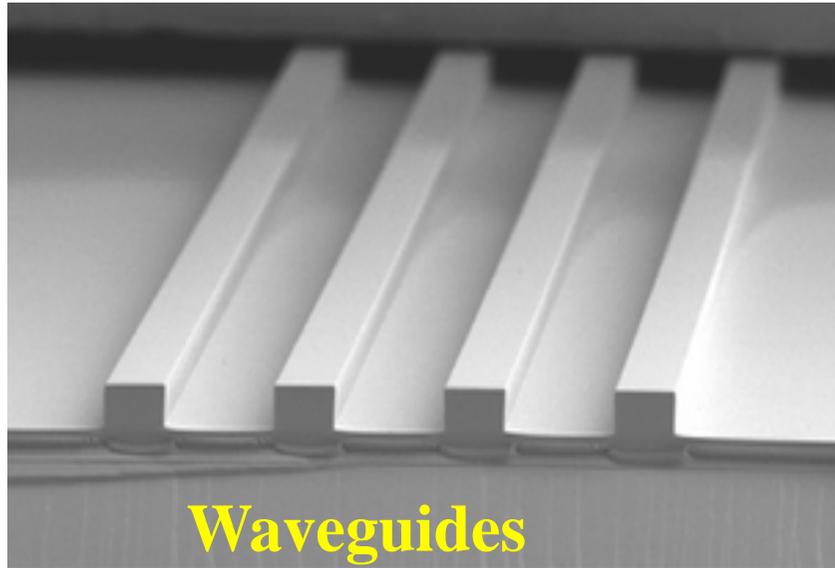


Highly versatile active material for optical devices

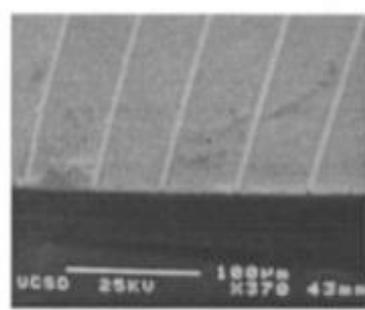
- Decoupled synthesis of NCs from preparation of matrix
- Complete tunability of optical properties from UV to IR range
- Full control on the device geometry/Selective localization of emitters
with nanometer scale resolution



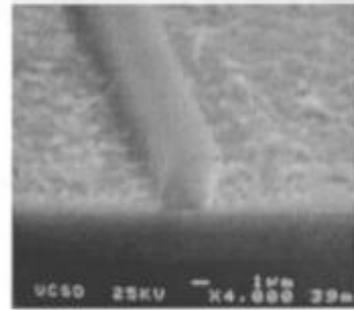
Building blocks for photonic devices



Building blocks for photonic devices



(a)

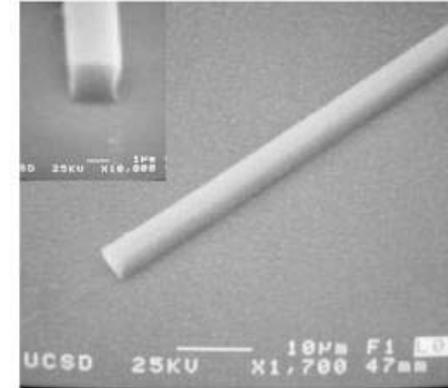


(b)

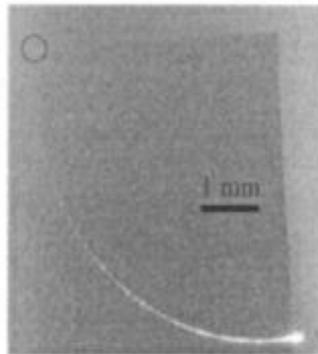
PMMA/NCs



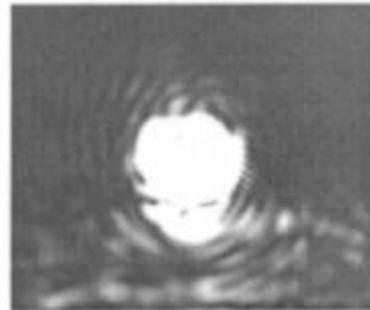
Waveguides



(a)

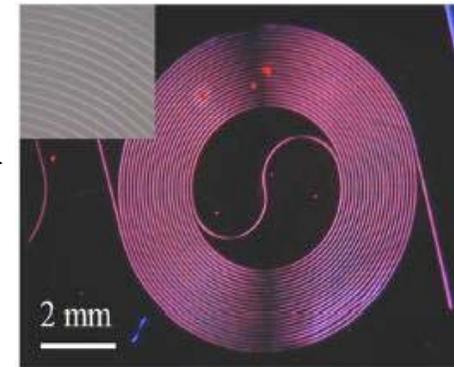


(c)



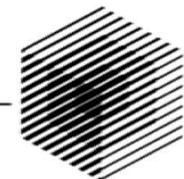
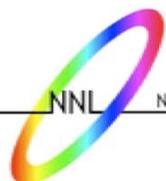
(d)

SU-8/NCs



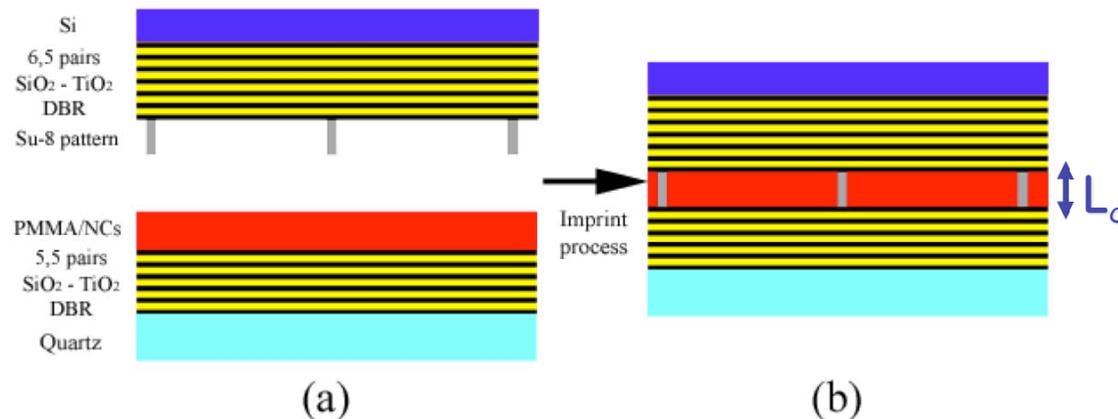
(b)

L.Pang et al., “*Photosensitive quantum dot composites and their applications in optical structures*”,
J. Vac. Sci. Technol. B 23, p. 2413 (2005)



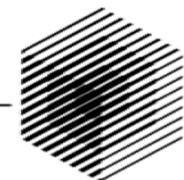
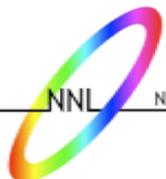
Colloidal QDs: vertical microcavity by hot embossing

- Unconventional use of **hot embossing** techniques
- **Colloidal CdSe/ZnS nanocrystals dispersed in a polymeric matrix (PMMA)**
- **Thermoplastic behavior of PMMA** exploited in order to define the device geometry

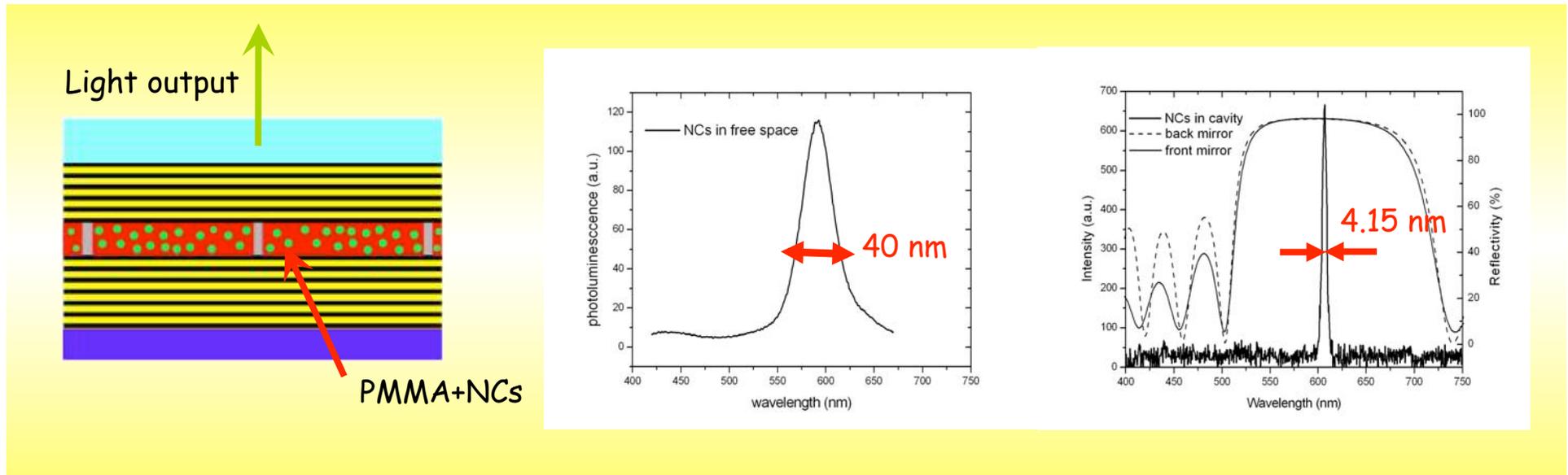


High-temperature exposure: 10' to 180°C → No damage of the optical properties of QDs

Insertion of SU-8 spacers between the mirrors → Good control of the cavity length L_c



Colloidal QDs: hybrid vertical microcavity by hot embossing



$$Q = 146$$



Localization of NCs by EBL processes

Blend deposition



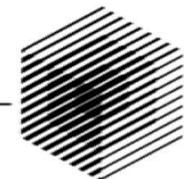
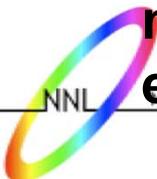
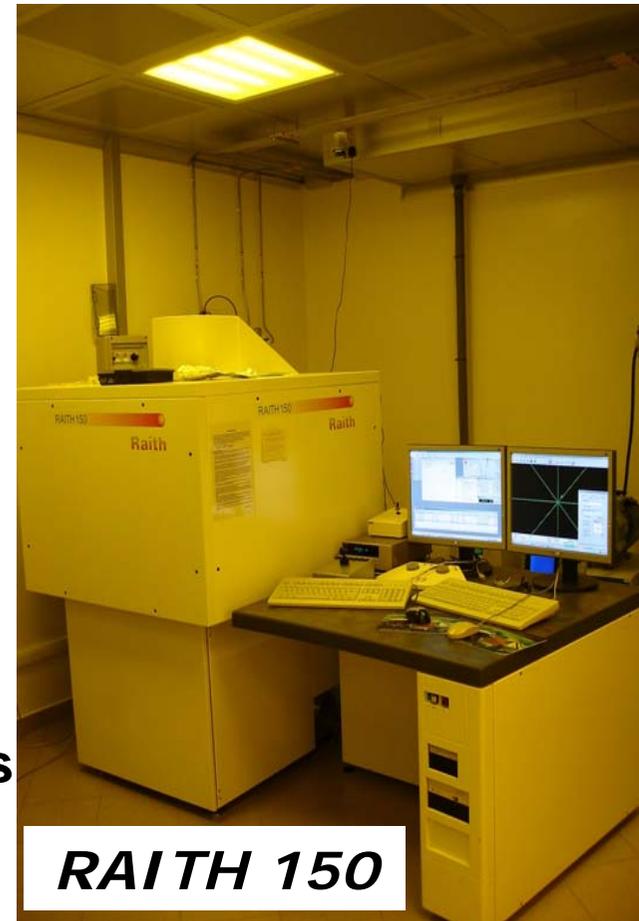
EBL exposure



Blend development

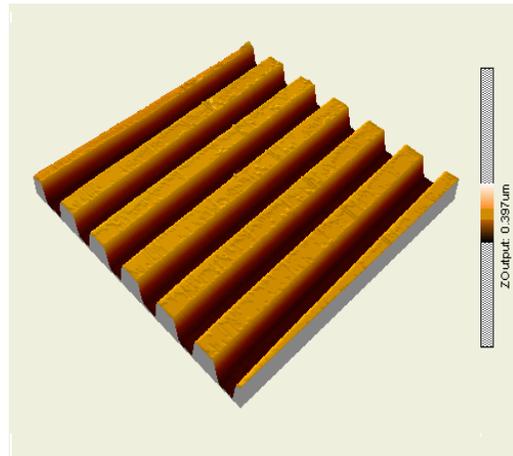
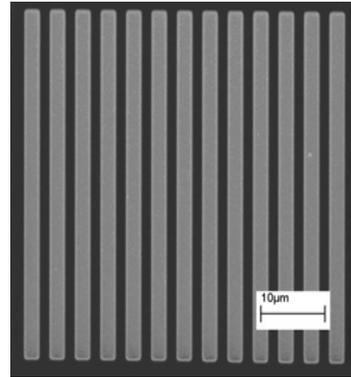


- Polymer/NCs blend still behaves as a resist
- Emission properties of NCs must not be affected by electron beam exposures

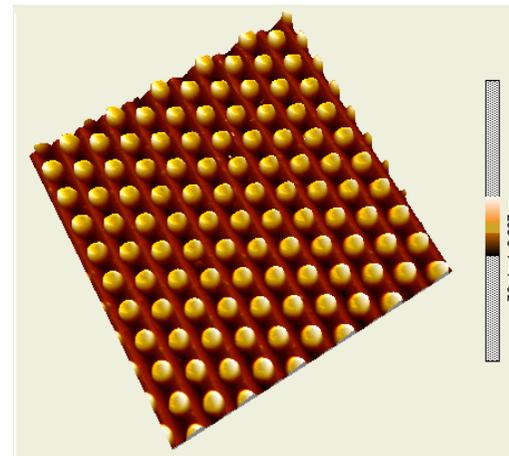
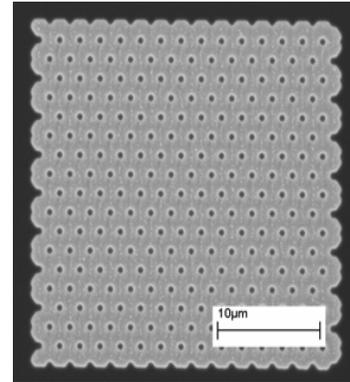


SEM and AFM images of patterned blend

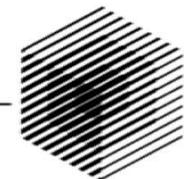
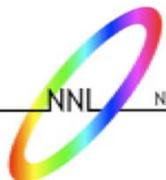
Stripes:
width=2 μ m
period=4 μ m



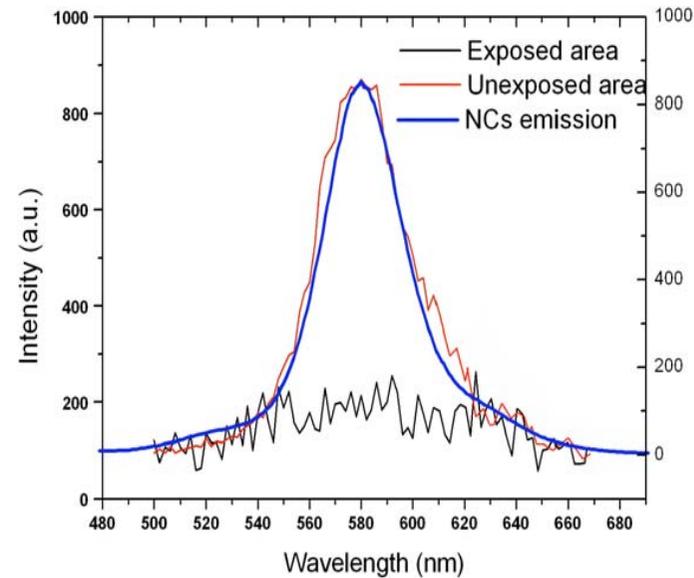
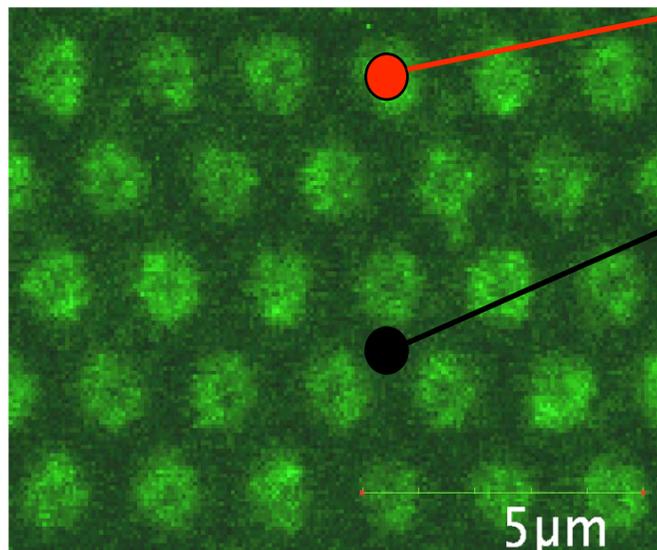
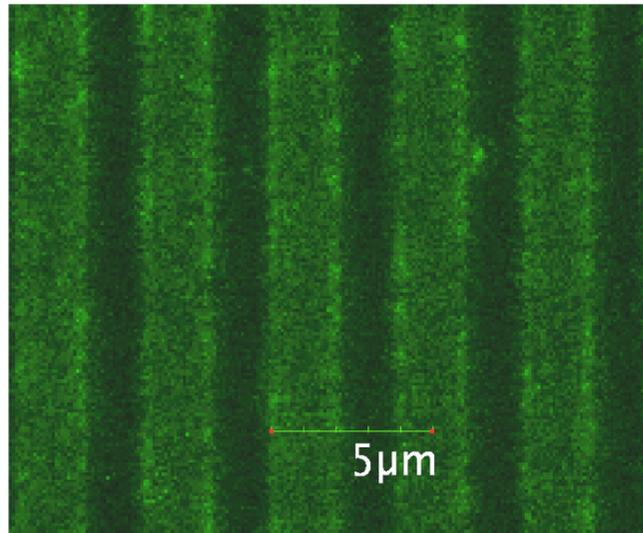
Pillars:
diameter=0.6 μ m
Period=2 μ m



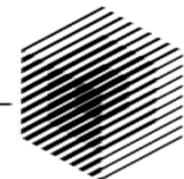
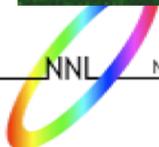
The positive resist behaviour of PMMA is not perturbed by the presence of NCs



Photoluminescence maps by confocal microscope



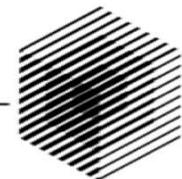
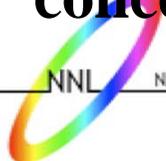
The emission spectrum
PL signal is detected
of NCs is not affected
only in the unexposed
by EBL
regions



NCs localization by lithographic techniques

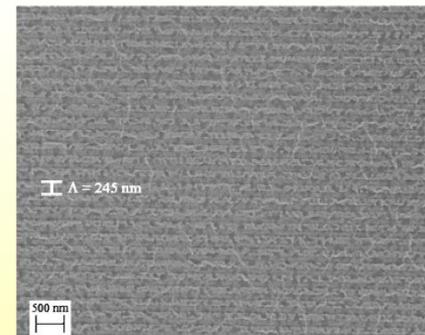
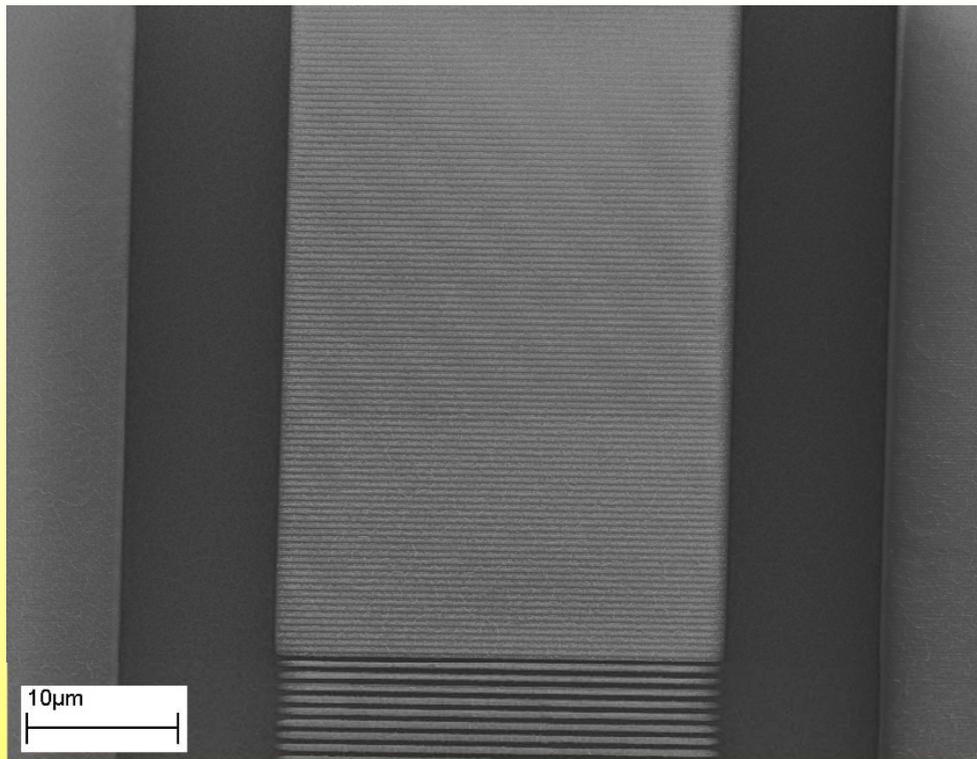
Several advantages:

- any kind of substrate without recurring to chemical or physical treatment of the surfaces;**
- not only rigid substrates but also flexible devices;**
- the typical resolution is defined by the lithographic process;**
- the density of emitters can be easily tuned by varying the relative molar concentration of the two components (NCs – resist);**
- processing by standard photolithographic techniques;**
- refractive index of the blend tunable with the NCs concentration.**

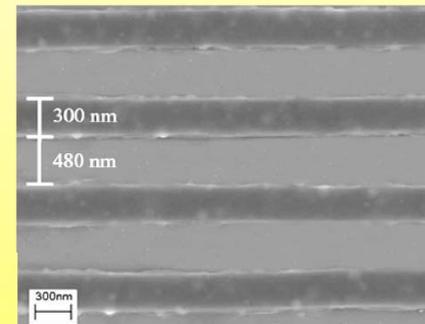


Colloidal QDs: Patterning of colloidal QDs by lithographic techniques

Building blocks for photonic devices



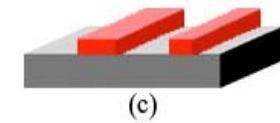
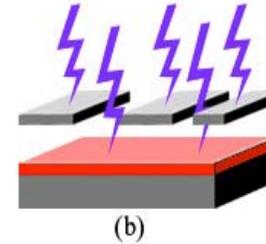
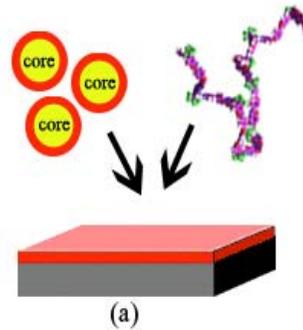
DFB
 $L_{\text{BRAGG}} = 245 \text{ nm}$
 $\text{thk} = 40 \text{ nm}$



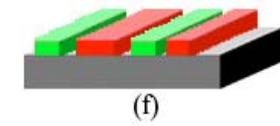
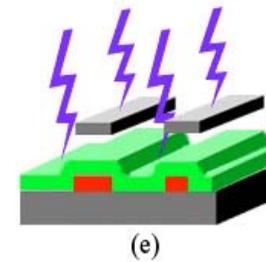
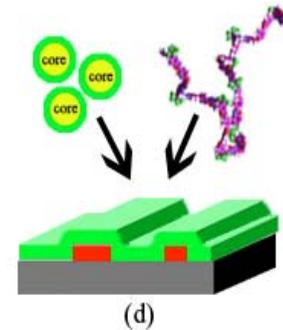
DBR
 $3\lambda/4$
stripes
 $\text{thk} =$
400nm

Easy implementation of multi-wavelength devices

lithographic process on 1st NCs ensemble

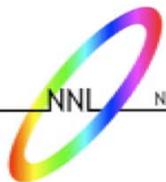


aligned lithographic process on 2nd NCs ensemble

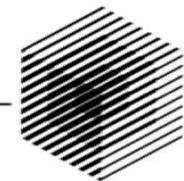


Re-aligned lithography

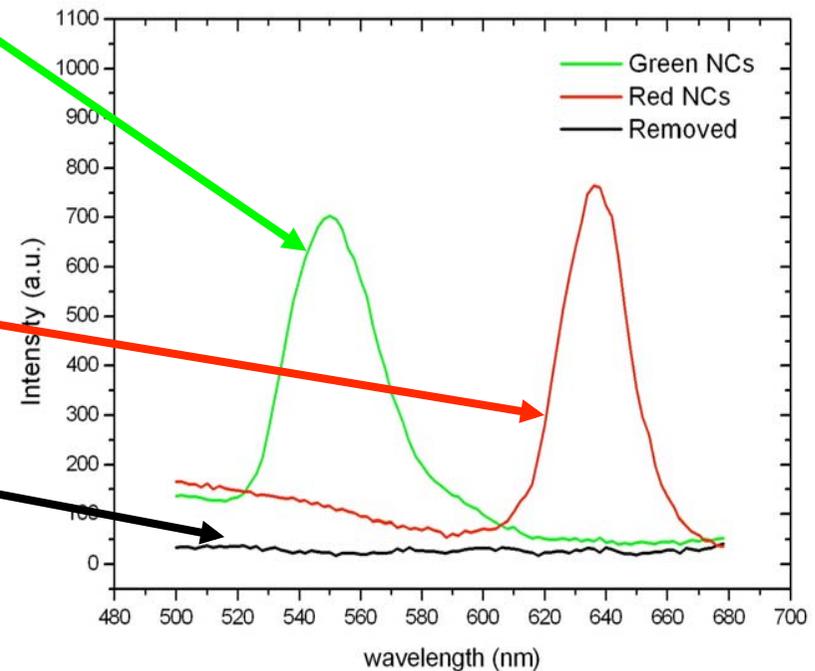
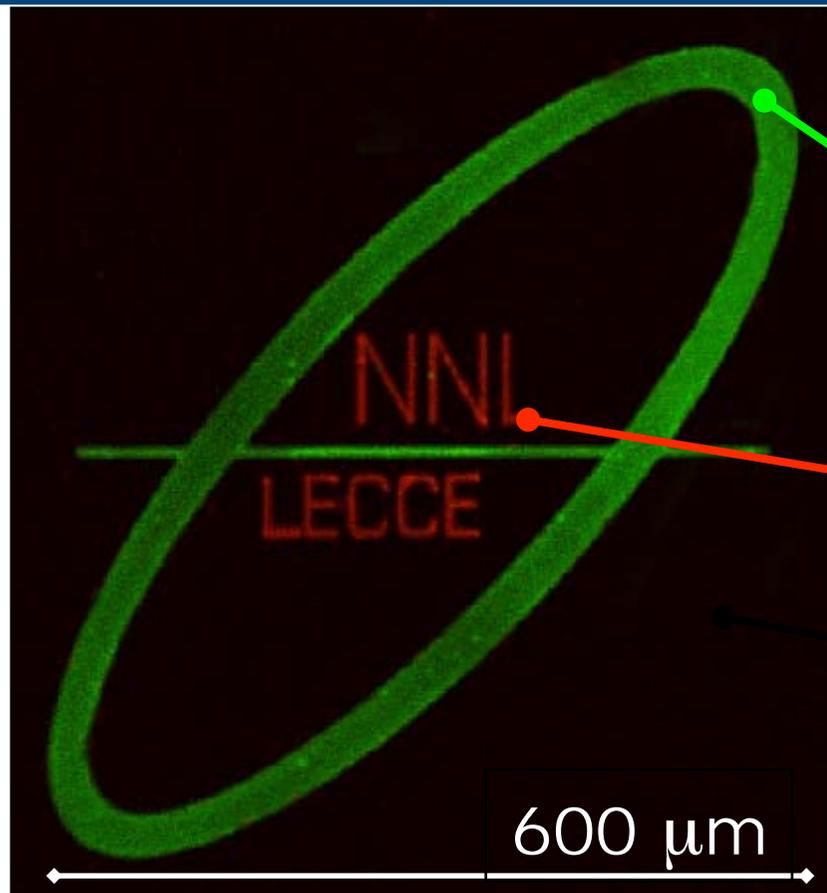
Localization of NCs emitting at different wavelengths on near or superimposed regions



National Nanotechnology Laboratory of T.N.F.R.C.



Easy implementation of multi-wavelength

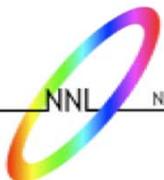


- 1st lithography: SU-8/red NCs ($\lambda_{\text{peak}}=640 \text{ nm}$, $M_{\text{NCs}}=3.5 \cdot 10^{-6}$

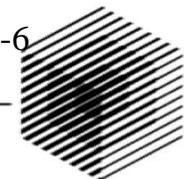
mol/l)

- 2nd lithography: SU-8/green NCs ($\lambda_{\text{peak}}=550 \text{ nm}$, $M_{\text{NCs}}=7.2 \cdot 10^{-6}$

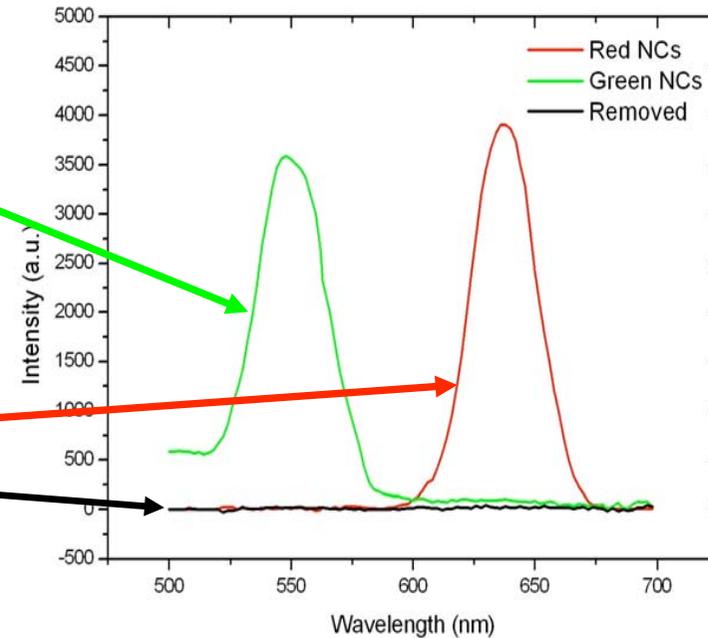
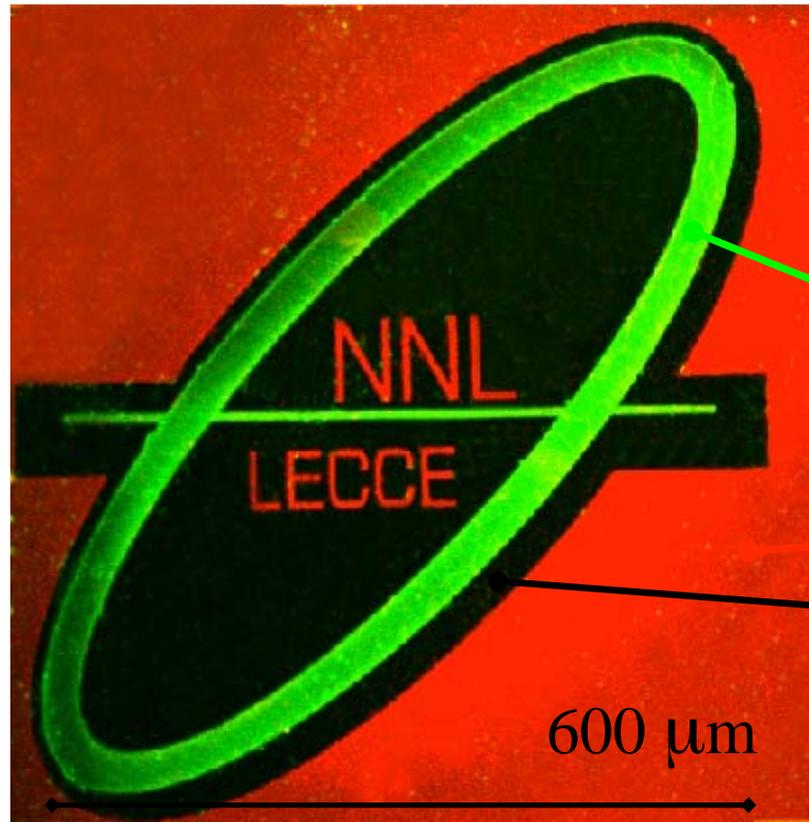
mol/l)



National Nanotechnology Laboratory of I.N.F.M.

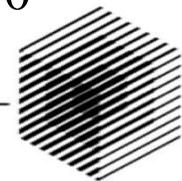


Easy implementation of multi-wavelength

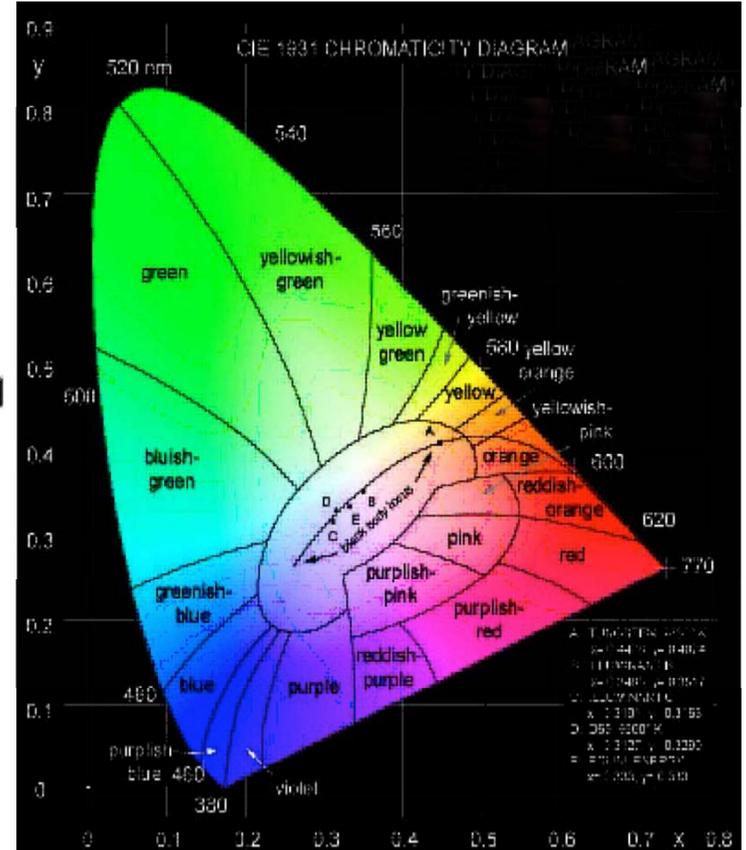
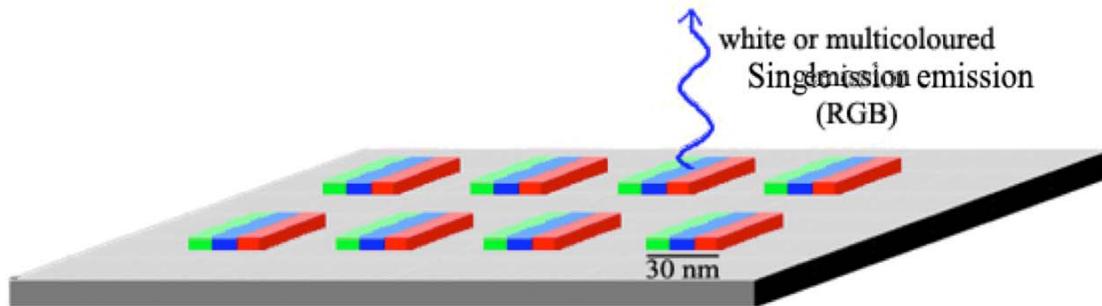


- 1st e-beam lithography: PMMA/red NCs ($\lambda_{\text{peak}}=640$ nm, $M_{\text{NCs}}=2.5 \cdot 10^{-5}$ mol/l)

- 2nd photolithography: SU-8/green NCs ($\lambda_{\text{peak}}=550$ nm, $M_{\text{NCs}}=7.2 \cdot 10^{-6}$ mol/l)



Easy implementation of multi-wavelength devices



Single colour nanoparticles

Multicoloured nanoparticles

White emitting nanoparticles

Relative intensities of R, G and B tunable with NCs concentration and pattern dimensions

